

Title (en)

SELF-STOPPING POLISHING COMPOSITION AND METHOD FOR BULK OXIDE PLANARIZATION

Title (de)

SELBSTSTOPPENDE POLIERZUSAMMENSETZUNG UND VERFAHREN ZUR OXIDMASSENPLANARISIERUNG

Title (fr)

COMPOSITION DE POLISSAGE À AUTO-ARRÊT ET PROCÉDÉ DE PLANARISATION D'OXYDE EN MASSE

Publication

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Application

EP 18788475 A 20180323

Priority

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Abstract (en)

[origin: WO2018194792A1] The invention provides a chemical-mechanical polishing composition comprising an abrasive, a self-stopping agent, an aqueous carrier, and optionally, a cationic polymer, and provides a method suitable for polishing a substrate.

IPC 8 full level

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CPC (source: CN EP KR)

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Citation (search report)

- [X] WO 2017011451 A1 20170119 - CABOT MICROELECTRONICS CORP [US]
- [X] KR 20140085265 A 20140707 - CHEIL IND INC [KR]
- See also references of WO 2018194792A1

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